

Sheet 1 of 5

Form PTO-1448 <b>U.S. DEPARTMENT OF COMMERCE</b> <b>PATENT AND TRADEMARK OFFICE</b> <b>LIST OF ART CITED BY APPLICANT</b> <small>(Use several sheets if necessary)</small>				#13	ATTY DOCKE L.O. MI22-1398	SERIAL NO. 09/536,037
				APPLICANT Weimin (Michael) Li et al.		
				FILING DATE March 27, 2000	GROUP 2822	
<b>U.S. PATENT DOCUMENTS</b>						
Examiner	Document Number	Date	Name		Class	Subclass
TMT	AA 4,474,975	10-2-1984	Clamons et al.		556	410
	AB 5,952,581	10-5-1999	Hayase et al.		524	588
	AC 4,805,883	2-21-1989	Magdo et al.		316	40
	AD 5,874,367	2-23-1999	Dobson		438	787
	AE 5,858,880	1-12-1999	Dobson et al.		438	758
	AF 5,219,813	6-15-1993	Fabry et al.		438	758
	AG 5,270,267	12-14-1993	Quillet		438	597
	AH 5,541,445	7-30-1996	Quillet		438	761
	AI 6,022,404	2-8-2000	Ettlinger et al.		106	404
	AJ 5,708,741	1-20-1998	Akamatsu et al.		106	387,11
	AK 4,648,904	3-10-1987	DePasquale et al.		106	2
	AL 4,158,717	6-19-1979	Nelson		428	446
	AM 5,667,015	9-16-1997	Harestad et al.		166	383
	AN 5,661,093	8-28-1997	Ravi et al.		438	763
	AO 5,536,857	7-16-1996	Nerula et al.		556	10
	AP 4,695,859	9-22-1987	Gupta et al.		257	64
	AQ 5,061,509	10-29-1991	Naito et al.		427	497
	AR 4,800,671	7-15-1986	Saitoh et al.		430	57.5
	AS 5,753,320	5-19-1998	Mikoshiba et al.		427	570
	AT 5,358,515	10-16-1994	Tahara et al.		438	715
	AU 4,954,867	9-4-1990	Hosaka		257	639
	AV 5,674,358	10-7-1997	Negayama		438	694
	AW 5,731,242	3-24-1998	Parat et al.		438	586
TMT	AX 5,741,721	4-21-1998	Stevens		438	396
EXAMINER				DATE CONSIDERED		
T. M. Thomas				12-07-01		
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<b>U.S. PATENT DOCUMENTS</b> <table border="1"> <thead> <tr> <th>Examiner</th> <th>Document Number</th> <th>Date</th> <th colspan="2">Name</th> <th>Class</th> <th>Subclass</th> <th colspan="2">Filing Date If Appropriate</th> </tr> </thead> <tbody> <tr><td>TMT</td><td>AA 5,034,348</td><td>7-23-1991</td><td colspan="2">Harlewick et al.</td><td>438</td><td>453</td><td colspan="2"></td></tr> <tr><td></td><td>AB 5,472,827</td><td>12-5-1995</td><td colspan="2">Ogawa et al.</td><td>430</td><td>315</td><td colspan="2"></td></tr> <tr><td></td><td>AC 5,472,828</td><td>12-5-1995</td><td colspan="2">Ogawa</td><td>430</td><td>325</td><td colspan="2"></td></tr> <tr><td></td><td>AD 5,641,607</td><td>6-24-1997</td><td colspan="2">Ogawa et al.</td><td>430</td><td>372,1</td><td colspan="2"></td></tr> <tr><td></td><td>AE 5,648,202</td><td>7-15-1997</td><td colspan="2">Ogawa et al.</td><td>430</td><td>325</td><td colspan="2"></td></tr> <tr><td></td><td>AF 5,871,297</td><td>9-23-1997</td><td colspan="2">Ogawa et al. Koppe et al.</td><td>382</td><td>293</td><td colspan="2"></td></tr> <tr><td></td><td>AG 5,877,111</td><td>10-14-1997</td><td colspan="2">Ogawa</td><td>430</td><td>313</td><td colspan="2"></td></tr> <tr><td></td><td>AH 5,898,352</td><td>12-16-1997</td><td colspan="2">Ogawa et al.</td><td>430</td><td>14</td><td colspan="2"></td></tr> <tr><td></td><td>AI 5,831,321</td><td>11-3-1998</td><td colspan="2">Nagayama</td><td>257</td><td>412</td><td colspan="2"></td></tr> <tr><td></td><td>AJ 5,591,566</td><td>1-7-1997</td><td colspan="2">Ogawa</td><td>430</td><td>325</td><td colspan="2"></td></tr> <tr><td></td><td>AK 6,008,124</td><td>12-28-1999</td><td colspan="2">Sakiguchi et al.</td><td>438</td><td>653</td><td colspan="2"></td></tr> <tr><td></td><td>AL 5,340,621</td><td>6-23-1994</td><td colspan="2">Matsumoto et al.</td><td>427</td><td>571</td><td colspan="2"></td></tr> <tr><td></td><td>AM 5,600,185</td><td>2-4-1997</td><td colspan="2">Tsukamoto et al.</td><td>257</td><td>323</td><td colspan="2"></td></tr> <tr><td></td><td>AN 5,872,385</td><td>2-16-1999</td><td colspan="2">Taft et al.</td><td>257</td><td>437</td><td colspan="2"></td></tr> <tr><td></td><td>AO 5,960,289</td><td>9-28-1999</td><td colspan="2">Tsui et al.</td><td>438</td><td>275</td><td colspan="2"></td></tr> <tr><td></td><td>AP 5,868,324</td><td>10-19-1998</td><td colspan="2">Cheung et al</td><td>204</td><td>192,28</td><td colspan="2"></td></tr> <tr><td></td><td>AQ 6,020,243</td><td>2-1-2000</td><td colspan="2">Wallace et al.</td><td>438</td><td>287</td><td colspan="2"></td></tr> <tr><td></td><td>AR 5,441,787</td><td>6-16-1995</td><td colspan="2">Hogan et al.</td><td>428</td><td>209</td><td colspan="2"></td></tr> <tr><td></td><td>AS 5,710,067</td><td>1-20-1998</td><td colspan="2">Fazio et al.</td><td>438</td><td>636</td><td colspan="2"></td></tr> <tr><td></td><td>AT 5,759,755</td><td>6-2-1998</td><td colspan="2">Park et al.</td><td>430</td><td>512</td><td colspan="2"></td></tr> <tr><td></td><td>AU 5,838,052</td><td>11-17-1998</td><td colspan="2">McTeer</td><td>257</td><td>437</td><td colspan="2"></td></tr> <tr><td></td><td>AV 5,883,011</td><td>3-16-1999</td><td colspan="2">Lin et al.</td><td>438</td><td>747</td><td colspan="2"></td></tr> <tr><td></td><td>AW 6,140,151</td><td>10-31-2000</td><td colspan="2">Akram</td><td>438</td><td>113</td><td colspan="2"></td></tr> <tr><td>TMT</td><td>AX 5,314,724</td><td>5-24-1994</td><td colspan="2">Tsukune et al.</td><td>427</td><td>489</td><td colspan="2"></td></tr> </tbody> </table>									Examiner	Document Number	Date	Name		Class	Subclass	Filing Date If Appropriate		TMT	AA 5,034,348	7-23-1991	Harlewick et al.		438	453				AB 5,472,827	12-5-1995	Ogawa et al.		430	315				AC 5,472,828	12-5-1995	Ogawa		430	325				AD 5,641,607	6-24-1997	Ogawa et al.		430	372,1				AE 5,648,202	7-15-1997	Ogawa et al.		430	325				AF 5,871,297	9-23-1997	Ogawa et al. Koppe et al.		382	293				AG 5,877,111	10-14-1997	Ogawa		430	313				AH 5,898,352	12-16-1997	Ogawa et al.		430	14				AI 5,831,321	11-3-1998	Nagayama		257	412				AJ 5,591,566	1-7-1997	Ogawa		430	325				AK 6,008,124	12-28-1999	Sakiguchi et al.		438	653				AL 5,340,621	6-23-1994	Matsumoto et al.		427	571				AM 5,600,185	2-4-1997	Tsukamoto et al.		257	323				AN 5,872,385	2-16-1999	Taft et al.		257	437				AO 5,960,289	9-28-1999	Tsui et al.		438	275				AP 5,868,324	10-19-1998	Cheung et al		204	192,28				AQ 6,020,243	2-1-2000	Wallace et al.		438	287				AR 5,441,787	6-16-1995	Hogan et al.		428	209				AS 5,710,067	1-20-1998	Fazio et al.		438	636				AT 5,759,755	6-2-1998	Park et al.		430	512				AU 5,838,052	11-17-1998	McTeer		257	437				AV 5,883,011	3-16-1999	Lin et al.		438	747				AW 6,140,151	10-31-2000	Akram		438	113			TMT	AX 5,314,724	5-24-1994	Tsukune et al.		427	489		
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<p style="text-align: center;">U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE</p> <p style="text-align: center;">LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)</p> <p style="text-align: right;"># 13</p>					ATTY. DOCK # O. MI22-1398	SERIAL NO. 09/536,037	
					APPLICANT Weimin (Michael) Li et al.		
<p style="text-align: center;">FILING DATE March 27, 2000</p>					GROUP 2822		
U.S. PATENT DOCUMENTS							
Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
TMT	AA	5,376,591	12-27-1994	Maeda et al.	438	761	
	AB	5,817,549	10-6-1998	Yemazaki et al.	438	166	
	AC	6,001,741	12-14-1999	Aliers	438	706	
	AD	6,072,227	6-6-2000	Yau et al.	357	642	
TMT	AE	6,786,039	7-20-1998	Brouquet	407	578	
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<small>1449</small> <small>SEP 04 2001</small> <b>LIST OF ART CITED BY APPLICANT</b> <small>(Use several sheets if necessary)</small>				<b>ATTY. DOCK #</b> MI22-1398 <b>APPLICANT</b> Weimin (Michael) Li et al. <b>FILING DATE</b> March 27, 2000 <b>GROUP</b> 2822	<b>SERIAL NO.</b> 08/538,037		
<b>FOREIGN PATENT DOCUMENTS</b>							
Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
TMT	AA	06067019A	9/1999	Japan (Glass)(Abstract)			
	AB	6-244172	9/1994	Japan			
	AC	593,727	10/1967	GB			
	AD	5-263255	10/1993	Japan			
	AE	0 471 185 A2	7/10/91	EPO			
	AF	0 588 087 A2	8/18/93	EPO			
	AG	0 588 087 A3	8/18/93	EPO			
	AH	09055351	23/2/97	Japan			
	AI	0 778 496 A2	05/12/96	EPO			
	AJ	20029	US99	Search Report			
	AK	20030	US99	Search Report			
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Form PTO-1449 <i>CIPS</i> <b>LIST OF ART CITED BY APPLICANT</b> (Use several sheets if necessary) SEP 04 2001			<b>ATTY. DOCKE J.O.</b> MI22-1388 <b>APPLICANT</b> Weimin (Michael) Li et al. <b>FILING DATE</b> March 27, 2000	<b>SERIAL NO.</b> 09/536,037 <b>GROUP</b> 2822
<b>OTHER REFERENCES</b> (Including Author, Title, Date, Pertinent Pages, Etc.) Examiner: <i>TMT</i>				
			Name	
	AA		TEXT: Jenkins, F. et al., "Fundamentals of Optics", Properties of Light, pp. 9-10. (No date)	
	AB		TEXT: Wong, S. et al., "Silicon Processing for the VLSI Era", Vol. 1, pp. 437-441. (No date)	
	AC		D.R. McKenzie et al., "New Technology for PACVO", Surface and Coatings Technology, 62 (1998), pp. 326-333.	
	AD		S. McClatchie et al., "Low Dielectric Constant Flowfill® Technology For IMD Applications"; undated; 7 pages	
	AE		K. Beekmann et al., "Sub-micron Gap Fill and In-Situ Planarisation using Flowfill™ Technology"; October 1995; pp. 1-7	
	AF		A. Kiermasz, et al., "Planarisation for Sub-Micron Devices Utilising a New Chemistry", Electrotech, February 1995; 2 pages	
	AG		IBM Technical Disclosure Bulletin "Low-Temperature Deposition of SiO <sub>2</sub> , Si <sub>3</sub> N <sub>4</sub> or SiO <sub>2</sub> -Si <sub>3</sub> N <sub>4</sub> ", Vol. 28, No. 9, p. 4170, Feb. 1986.	
	AH		ARTICLE: Benchar, C. et al., "Dielectric antireflective coatings for DUV lithography", Solid State Technology (March 1997), pp.109-114.	
	AI		Noboru Shibata, "Plasma-Chemical Vapor-Deposited Silicon Oxide/Silicon Oxynitride Double-Layer Antireflective Coating for Solar Cells", Japanese Journal of Applied Physics, Vol. 30, No. 5, May 1991, pp. 997-1001.	
	AJ		Ralls, Kenneth M., "Introduction to Materials Science and Engineering", John Wiley & Sons, © 1976, pp. 312-313	
	AK		Ravi K. Laxman, "Synthesizing Low-k CVD Materials for Fab Use", Semiconductor International, Nov. 2000, 10 pps.	
	AL		Anonymous, "New gas helps make faster IC's", Machine Design Cleveland, © Penton Media, Inc., November 4, 1999, pp. 118	
	AM		Loboda et al., "Using Trimethylsilane to Improve Safety Throughput and Versatility in PECVD Processes", 4th International Symposium on Silicon Nitride and Silicon Dioxide Thin Insulating Films, The Electrochemical Society, Abstract No. 358, p. 454, May 1997.	
	AN		ARTICLE: Dammel, R. R. et al., "Dependence of Optical Constants of AZ® BARLI™ Bottom Coating on Back Conditions", SPIE Vol. 3049 (1997), pp. 963-973.	
	AO		TEXT: Heavens, O. S., "Optical Properties of Thin Solid Films", pp. 48-49.	
	AP		Wilkman, R. et al., "Matrix Reactions of Methyisilanes and Oxygen Atoms", Phys. Chem 1988, pp. 594-602.	
	AQ		Weidman, T. et al., "New photodefinable glass etch masks for entirely dry photolithography: Plasma deposited organosilicon hydride polymers", Appl. Phys. Lett 1-25-93, pp. 372-374.	
	AR		Weidman, et al., "All Dry Lithography: Applications of Plasma Polymerized Methylsilane as a Single Layer Resist and Silicon Dioxide Precursor", Journal of Photopolymer Science and Technology, V. 8, #4, 1995, pp. 679-686.	
	AS		Joubert et al., "Application of Plasma Polymerized Methylsilane in an all dry resist process for 193 and 248 nm Lithography", Microelectronic Engineering 30 (1996), pp. 275-278.	
	AT		Joshi, A.M. et al., "Plasma Deposited Organosilicon Hydrido Network Polymers as Versatile Resists for Entirely Dry Mid-Deep UV Photolithography", SPIE Vol. 1925, pp. 709-720.	
	AU		Matsuura, M. et al., "Highly Reliable Self-Planarizing Low-k Intermetal Dielectric for Sub-quarter Micro Interconnects", IEEE 1997, pp. 785-788.	
	AV		Moris, O. et al., "Kinetics and Mechanism of the Reactions of ...", J. Phys. Chem 1991, 1393-400.	
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